10644954_CLS
Most Frequently Occurring Classifications of Patents Returned From A Search of 10644954 on July 28, 2004

Original Classifications

9	378/34
6	378/119
5	250/492.2
2	355/67
2	359/366
2	359/857

Cross-Reference Classifications

10	378/34
7	355/67
4	355/53
4	378/119
3	250/492.1
3	250/492.3
3	359/859
3	378/145
3	378/146
3	378/147
3	378/35
3	378/84
3	378/85
2	250/492.2
2	250/504R
2	257/E21.035
2	257/E21.279
2	359/366
2	359/858
2	359/861
2	378/143
2	430/396

Combined Classifications

19	378/34
10	378/119
9	355/67
7	250/492.2
5	355/53
4	250/492.1
4	359/366
4	359/859
4	378/85
3	250/492.3
3	359/857

3 359/858
3 378/145
3 378/146
3 378/147
3 378/35
3 378/84
2 250/492.22
2 250/504R
2 257/E21.035
2 257/E21.279
2 355/69
2 356/520
2 359/861
2 378/143
2 430/296
2 430/30
2 430/311
2 430/396

10644954_CLSTITLES

Titles of Most Frequently Occurring Classifications of Patents Returned

From A Search of 10644954 on July 28, 2004

19 378/34 (9 OR, 10 XR)
Class 378 : X-RAY OR GAMMA RAY SYSTEMS OR DEVICES
378/1 SPECIFIC APPLICATION
378/34 .Lithography

10 378/119 (6 OR, 4 XR)
Class 378 : X-RAY OR GAMMA RAY SYSTEMS OR DEVICES
378/119 SOURCE

9 355/67 (2 OR, 7 XR)
Class 355 : PHOTOCOPYING
355/18 PROJECTION PRINTING AND COPYING CAMERAS
355/67 .Illumination systems or details

7 250/492.2 (5 OR, 2 XR)
Class 250 : RADIANT ENERGY
250/492.1 IRRADIATION OF OBJECTS OR MATERIAL
250/492.2 .Irradiation of semiconductor devices

5 355/53 (1 OR, 4 XR)
Class 355 : PHOTOCOPYING
355/18 PROJECTION PRINTING AND COPYING CAMERAS
355/53 .Step and repeat

4 250/492.1 (1 OR, 3 XR)
Class 250 : RADIANT ENERGY
250/492.1 IRRADIATION OF OBJECTS OR MATERIAL

4 359/366 (2 OR, 2 XR)
Class 359 : OPTICS: SYSTEMS
359/362 COMPOUND LENS SYSTEM
359/364 .With curved reflective imaging element
359/365 ..Two or more in a series
359/366 ...Concave, convex combination

4 359/859 (1 OR, 3 XR)
Class 359 : OPTICS: SYSTEMS
359/838 MIRROR
359/850 .Plural mirrors or reflecting surfaces
359/857 ..With successive reflections
359/858 ...Including curved mirror surfaces in series
359/859 ....With concave and convex mirrors in series

4 378/85 (1 OR, 3 XR)
Class 378 : X-RAY OR GAMMA RAY SYSTEMS OR DEVICES
378/1 SPECIFIC APPLICATION
378/70 .Diffraction, reflection, or scattering analysis
378/82 ..Spatial energy dispersion
378/84 ...Monochromator or focusing device
378/85 ....With plural dispersing elements

3 250/492.3 (0 OR, 3 XR)
Class 250 : RADIANT ENERGY
250/492.1 IRRADIATION OF OBJECTS OR MATERIAL
250/492.3 .Ion or electron beam irradiation

3 359/857 (2 OR, 1 XR)
Class 359 : OPTICS: SYSTEMS
359/838 MIRROR
359/850 .Plural mirrors or reflecting surfaces
359/857 ..With successive reflections

3 359/858 (1 OR, 2 XR)
Class 359 : OPTICS: SYSTEMS
359/838 MIRROR
359/850 .Plural mirrors or reflecting surfaces
359/857 ..With successive reflections
359/858 ...Including curved mirror surfaces in series

3 378/145 (0 OR, 3 XR)
Class 378 : X-RAY OR GAMMA RAY SYSTEMS OR DEVICES
378/145 BEAM CONTROL

3 378/146 (0 OR, 3 XR)
Class 378 : X-RAY OR GAMMA RAY SYSTEMS OR DEVICES
378/145 BEAM CONTROL
378/146 .Scanner

3 378/147 (0 OR, 3 XR)
Class 378 : X-RAY OR GAMMA RAY SYSTEMS OR DEVICES
378/145 BEAM CONTROL
378/147 .Collimator

3 378/35 (0 OR, 3 XR)
Class 378 : X-RAY OR GAMMA RAY SYSTEMS OR DEVICES
378/1 SPECIFIC APPLICATION
378/34 .Lithography

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          378/35          ..Pattern mask

  3  378/84          (0 OR, 3 XR)
          Class    378 :  X-RAY OR GAMMA RAY SYSTEMS OR DEVICES
          378/1           SPECIFIC APPLICATION
          378/70          .Diffraction, reflection, or scattering
                               analysis
          378/82          ..Spatial energy dispersion
          378/84          ...Monochromator or focusing device

  2  250/492.22      (1 OR, 1 XR)
          Class    250 :  RADIANT ENERGY
          250/492.1       IRRADIATION OF OBJECTS OR MATERIAL
          250/492.2       .Irradiation of semiconductor devices
          250/492.22      ..Pattern control

  2  250/504R        (0 OR, 2 XR)
          Class    250 :  RADIANT ENERGY
          250/493.1       RADIANT ENERGY GENERATION AND SOURCES
          250/503.1       .With radiation modifying member
          250/504R        ..Ultraviolet or infrared source

  2  257/E21.035     (0 OR, 2 XR)
          Class    257 :  ACTIVE SOLID-STATE DEVICES
          257/E21.001     PROCESSES OR APPARATUS ADAPTED FOR MANUFACTURE

                               OR TREATMENT OF SEMICONDUCTOR OR SOLID-
STATE DEVICES OR OF
                               PARTS THEREOF (EPO)
          257/E21.002     .Manufacture or treatment of semiconductor
                               device (EPO)
          257/E21.023     ..Making mask on semicond uctor body for
                               further photolithographic processing (EPO
)
          257/E21.033     ...Comprising inorganic layer (EPO)
          257/E21.035     ....Characterized by their composition, e.g.,
                               multilayer masks, materials (EPO)

  2  257/E21.279     (0 OR, 2 XR)
          Class    257 :  ACTIVE SOLID-STATE DEVICES
          257/E21.001     PROCESSES OR APPARATUS ADAPTED FOR MANUFACTURE

                               OR TREATMENT OF SEMICONDUCTOR OR
SOLID-STATE DEVICES OR OF
                               PARTS THEREOF (EPO)
          257/E21.002     .Manufacture or treatment of semiconductor
                               device (EPO)
          257/E21.04      ..Device having at least one potential-jump
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barrier or surface barrier, e.g., PN junction, depletion layer, carrier concentration layer (EPO)

257/E21.085 ...Device having semiconductor body comprising Group IV elements or Group III-V compounds with or without impurities, e.g., doping materials (EPO)

257/E21.211 ....Treatment of semiconductor body using process other than deposition of semiconductor material on a substrate, diffusion or alloying of impurity material, or radiation treatment (EPO)

257/E21.214 .....To change their surface-physical characteristics or shape, e.g., etching, polishing, cutting (EPO)

257/E21.24 ......To form insulating layer thereon, e.g., for masking or by using photolithographic technique (EPO)

257/E21.266 ....Inorganic layer (EPO)

257/E21.271 ....Composed of oxide or glassy oxide or oxide based glass (EPO)

257/E21.274 ....Deposition from gas or vapor (EPO)

257/E21.278 ....Deposition of silicon oxide (EPO)

257/E21.279 ....On silicon body (EPO)

2 355/69 (1 OR, 1 XR)

Class 355 : PHOTOCOPYING

355/18 PROJECTION PRINTING AND COPYING CAMERAS

355/67 .Illumination systems or details

355/69 ..Electricity to lamp controlled

2 356/520 (1 OR, 1 XR)

Class 356 : OPTICS: MEASURING AND TESTING

356/450 ~~BY LIGHT INTERFERENCE (E.G., INTERFEROMETER)~~

356/520 .Having shearing

2 359/861 (0 OR, 2 XR)

Class 359 : OPTICS: SYSTEMS

359/838 MIRROR

359/850 .Plural mirrors or reflecting surfaces

359/857 ..With successive reflections

359/861 ...With three or more successive reflections

2 378/143 (0 OR, 2 XR)
Class 378 : X-RAY OR GAMMA RAY SYSTEMS OR DEVICES
378/119 SOURCE
378/143 .Target

2 430/296 (1 OR, 1 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS, COMPOSITION, OR PRODUCT THEREOF
430/269 IMAGING AFFECTING PHYSICAL PROPERTY OF RADIATION SENSITIVE MATERIAL, OR PRODUCING NONPLANAR OR PRINTING SURFACE - PROCESS, COMPOSITION, OR PRODUCT
430/296 .Electron beam imaging

2 430/30 (1 OR, 1 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS, COMPOSITION, OR PRODUCT THEREOF
430/30 INCLUDING CONTROL FEATURE RESPONSIVE TO A TEST OR MEASUREMENT

2 430/311 (1 OR, 1 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS, COMPOSITION, OR PRODUCT THEREOF
430/269 IMAGING AFFECTING PHYSICAL PROPERTY OF RADIATION SENSITIVE MATERIAL, OR PRODUCING NONPLANAR OR PRINTING SURFACE - PROCESS, COMPOSITION, OR PRODUCT
430/311 .Making electrical device

2 430/396 (0 OR, 2 XR)
Class 430 : RADIATION IMAGERY CHEMISTRY: PROCESS, COMPOSITION, OR PRODUCT THEREOF
430/396 EFFECTING FRONTAL RADIATION MODIFICATION DURING EXPOSURE, E,G., SCREENING, MASKING, STENCILING, ETC.